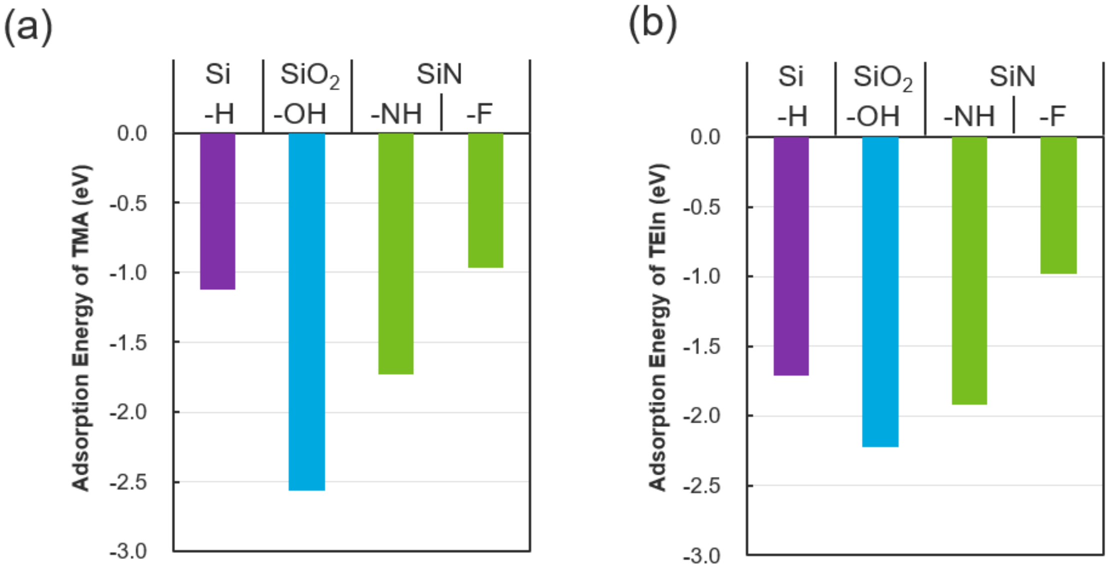

Fig.1 (a)Calculated adsorption energies of TMA on Si, SiO$_2$ and SiN surfaces.
(b)Calculated adsorption energies of TEIn on Si, SiO$_2$ and SiN surfaces.

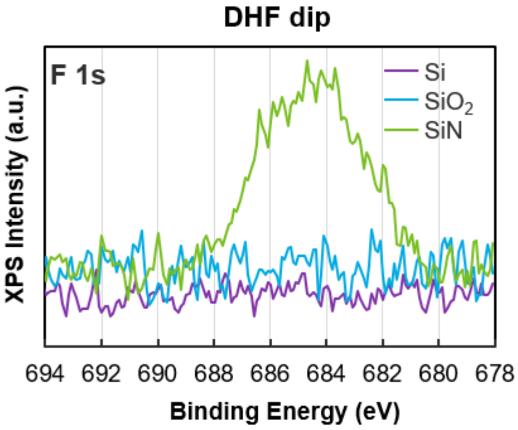

Fig.2 XPS F1s spectra of the Si, SiO$_2$, and SiN substrates after DHF dipping.

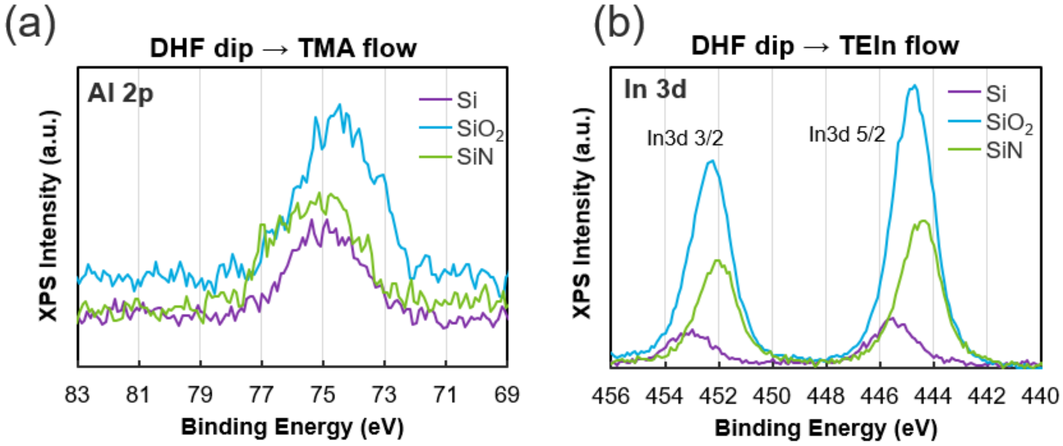

Fig.3 (a)XPS Al2p spectra of the Si, SiO_2, and SiN substrate after TMA introduction. (b)XPS In3d spectra of the Si, SiO_2, and SiN substrate after TEIn introduction.